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# KATE

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IATEX is a document preparation system for the TEX type setting program. It offers programmable desktop publishing features and extensive facilities for automating most aspects of type setting and desktop publishing, including numbering and cross-referencing, tables and figures, page layout, bibliographies, and much more. IATEX was originally written in 1984 by Leslie Lamport and has become the dominant method for using TEX; few people write in plain TEX anymore. The current version is IATEX  $2\varepsilon$ .

$$E_0 = mc^2 (1)$$

$$E = \frac{mc^2}{\sqrt{1 - \frac{v^2}{c^2}}}\tag{2}$$

### 1 Introduction

This text would appear just from the left side below the introduction Let's Begin with a formula  $e^{i\pi} + 1 = 0$ .

But we can also do

$$e = \lim_{n \to \infty} \left( 1 + \frac{1}{n} \right)^n = \lim_{n \to \infty} \frac{n}{\sqrt[n]{n!}}$$

we can do another:

$$e = \sum_{n=0}^{\infty} \frac{1}{n!}$$

### 2 Just another Section

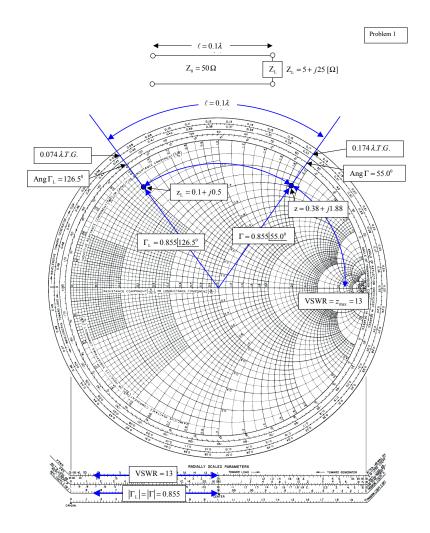
Just some text under this section

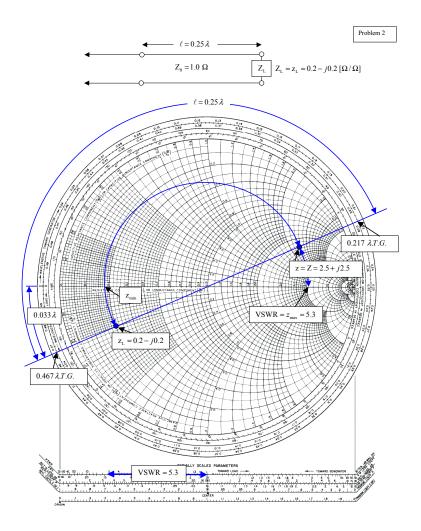
#### 2.1 A subsection

Whatever code put in here would be shown as same as they are written:

```
//Whatever code put in here would be shown as same as they are written
  class _WeatherPageState extends State<WeatherPage> {
    @override
    void initState() {
        getweather();
        super.initState();
    }

WeatherFactory wf = new WeatherFactory("9e8638e0e66018f75db6fc0ed9512f3b");
late Weather mylocation;
bool loading = true;
getweather() async {
        await Geolocator.requestPermission();
        print('gotlocation');
```





#### 2.2 next subsection

Text under subsection: putting some lorem ipsum to make it look like there is some text under this. Lorem Ipsum is simply dummy text of the printing and typesetting industry. Lorem Ipsum has been the industry's standard dummy text ever since the 1500s, when an unknown printer took a galley of type and scrambled it to make a type specimen book. It has survived not only five centuries, but also the leap into electronic typesetting, remaining essentially unchanged. It was popularised in the 1960s with the release of Letraset sheets containing Lorem Ipsum passages, and more recently with desktop publishing software like Aldus PageMaker including versions of Lorem Ipsum.

#### 2.2.1 a sub sub section:)

It is a long established fact that a reader will be distracted by the readable content of a page when looking at its layout. The point of using Lorem Ipsum is that it has a more-or-less normal distribution of letters, as opposed to using 'Content here, content here', making it look like readable English. Many desktop publishing packages and web page editors now use Lorem Ipsum as their default model text, and a search for 'lorem ipsum' will uncover many web sites still in their infancy. Various versions have evolved over the years, sometimes by accident, sometimes on purpose (injected humour and the like).

#### 2.2.2 second sub sub section

Lorem ipsum dolor sit amet, consectetur adipiscing elit, sed do eiusmod tempor [7] incididunt ut labore et dolore magna aliqua. Ut enim ad minim veniam, quis [4] nostrud exercitation ullamco laboris nisi ut aliquip ex ea commodo consequat.[3]

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## References

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